



*Summary of SOFC Development  
at Redox Power Systems for  
FE0027897 & FE0031656*

*3/2/2022*

*U.S. Department of Energy, National Energy Technology Laboratory's (NETL)  
Solid Oxide Fuel Cell (SOFC) Project Review Meeting*

*Bryan Blackburn, Ph.D.  
Redox Power Systems*



# Updates for FE0027897 & FE031656

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## **1. FE0027897:** *Red-ox robust SOFC stacks for affordable, reliable distributed generation power systems*

- Background (ceramic anode cell with a GDC electrolyte)
- Red-Ox cycling impact on material conductivity and cell OCV & Power
- Challenges balancing cell size, strength, and power density

## **2. FE0031656:** *Sputtered thin films for very high power, efficient, and low-cost commercial SOFCs*

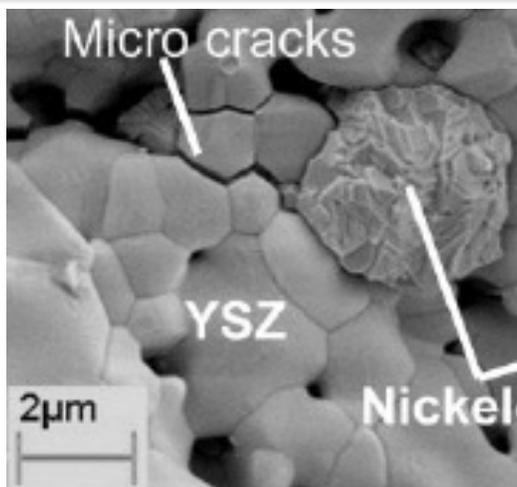
- Background (electron-blocking layer for GDC electrolyte SOFCs)
- Problems/solutions for achieving high OCV
- Problems/solutions for achieving low ASR

# FE0027897 Red-Ox Robust Stacks

Red-ox cycles can be expected during long-term fuel cell operation

- Interruptions in fuel supply
- Impact of small seal leaks over the long-term
- Transient SOFC operation
  - System shutdown
  - Very high fuel utilization events (e.g., extreme load following)

***Ni-cermet anodes prone to mechanical failure during redox cycling***

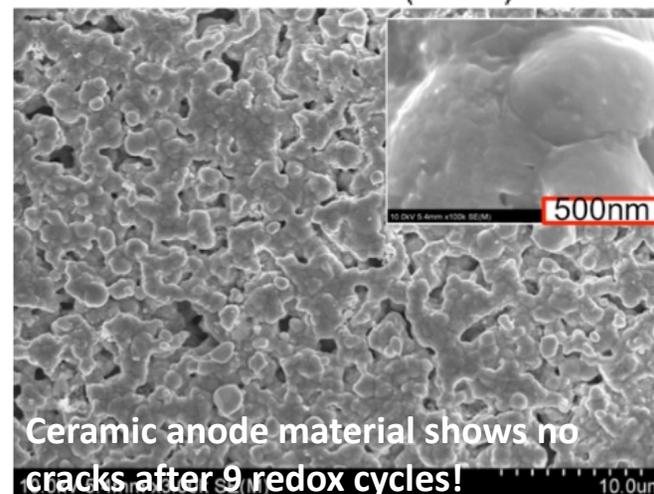
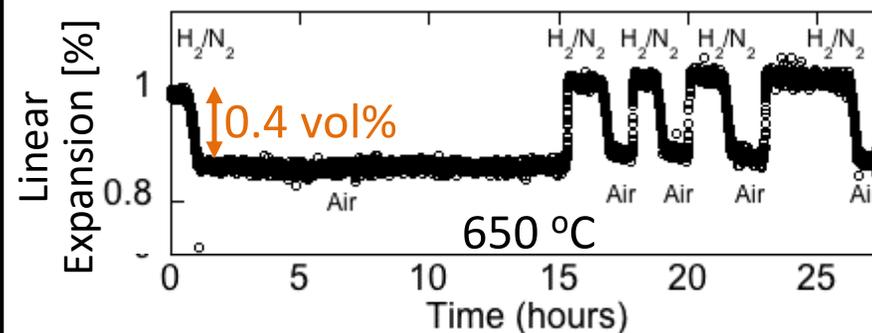


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~69 vol% expansion of Ni → NiO

Solution:

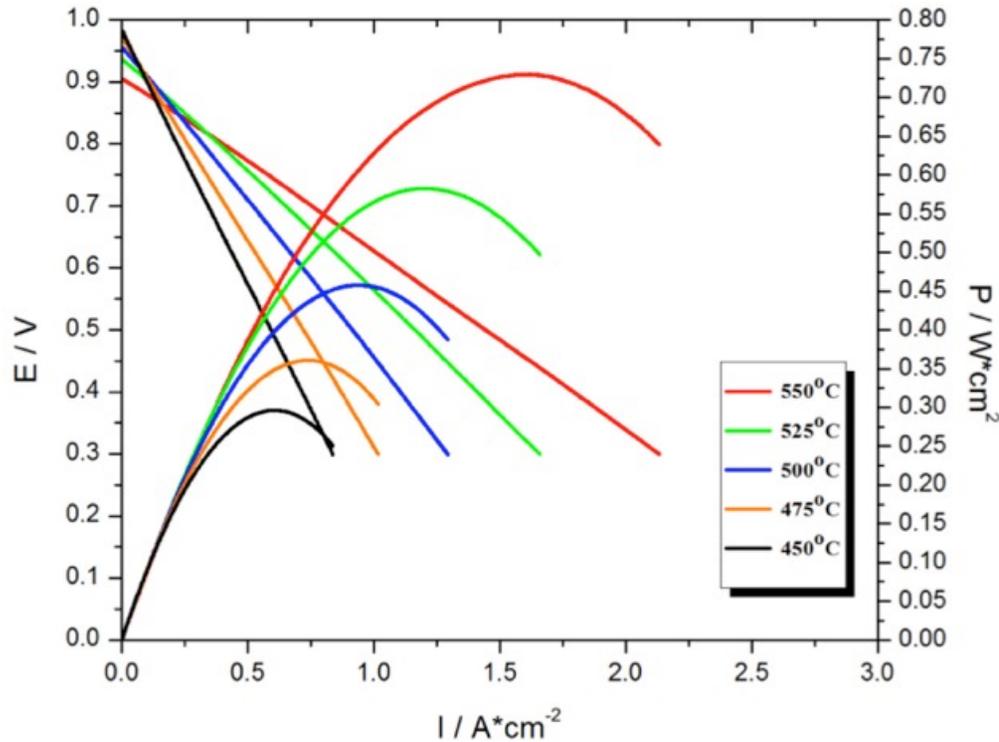
**Ceramic anode** → small  $\Delta$ oxygen = small dimensional change (0.4 vol%)



**Ceramic anode material shows no cracks after 9 redox cycles!**

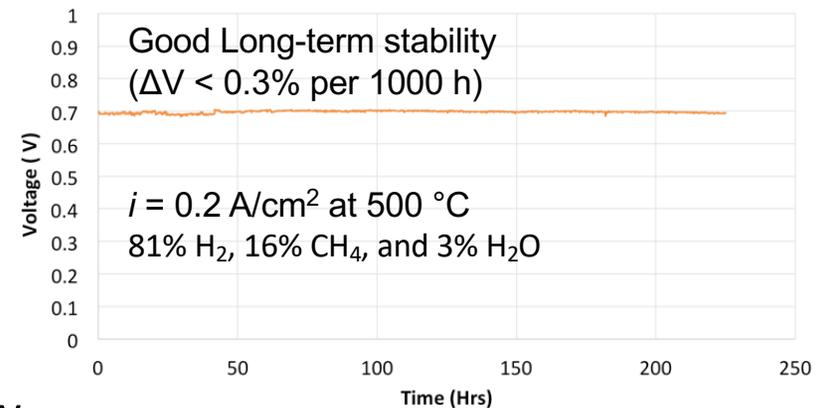
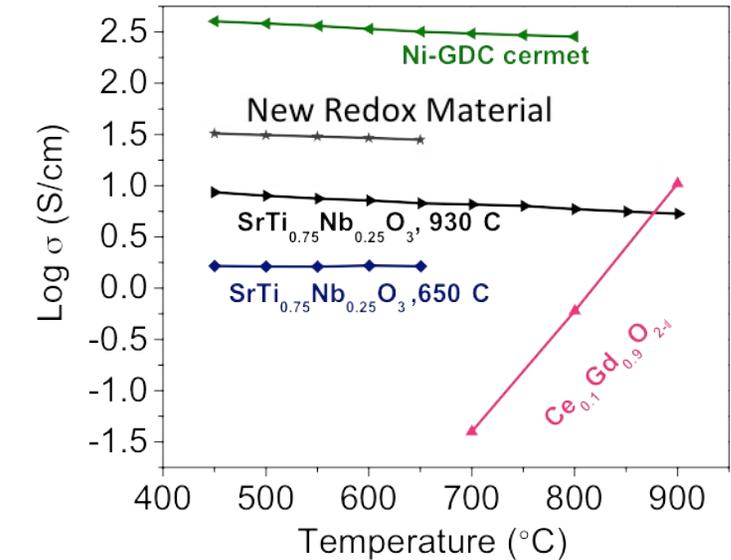
# REDOX All-Ceramic Anode Performance

Button cell data

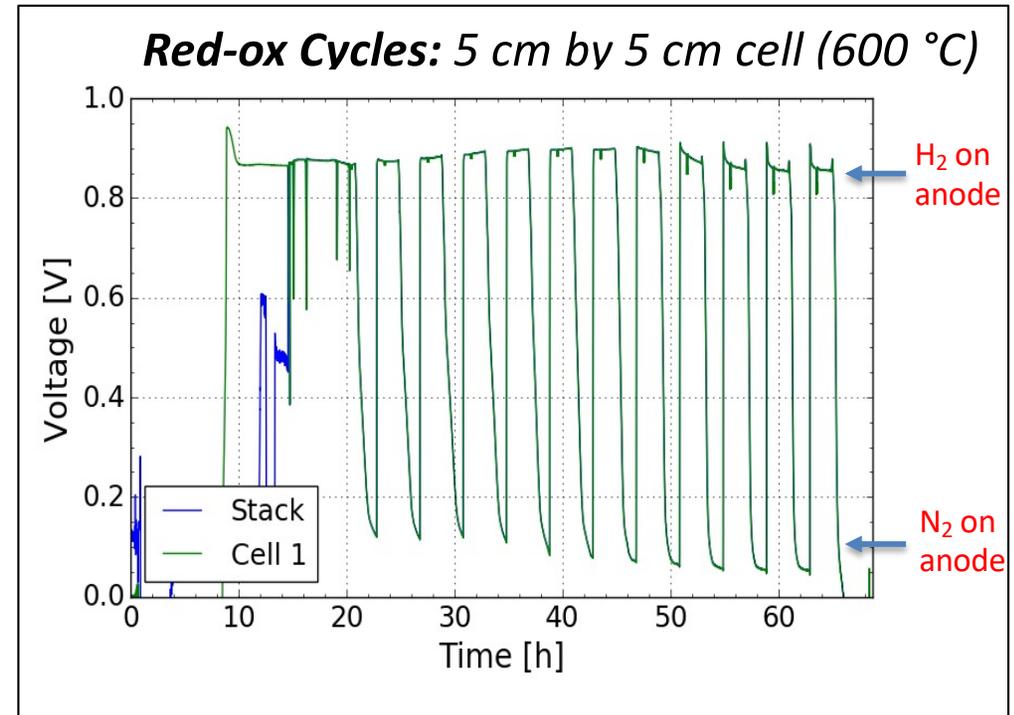
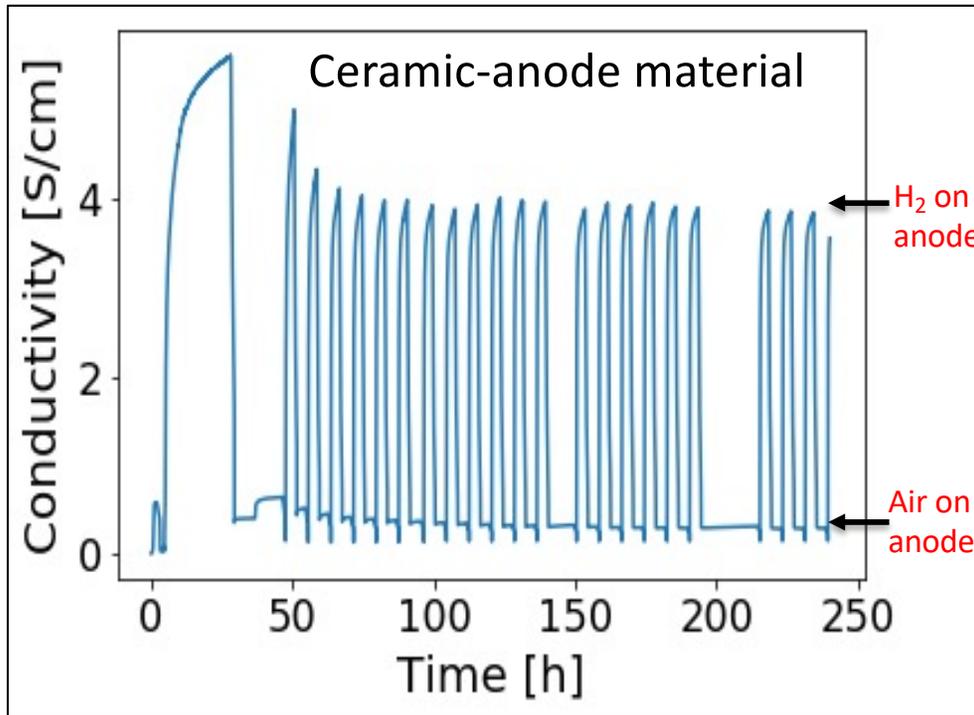


- High power densities
  - ~0.75 W/cm<sup>2</sup> @ 550°C
  - ~0.3 W/cm<sup>2</sup> @ 450 °C
- Reasonably high (acceptable) electronic conductivity
- Conductivity and electrochemical activity further boosted using anode infiltration

Anode electrical conductivity



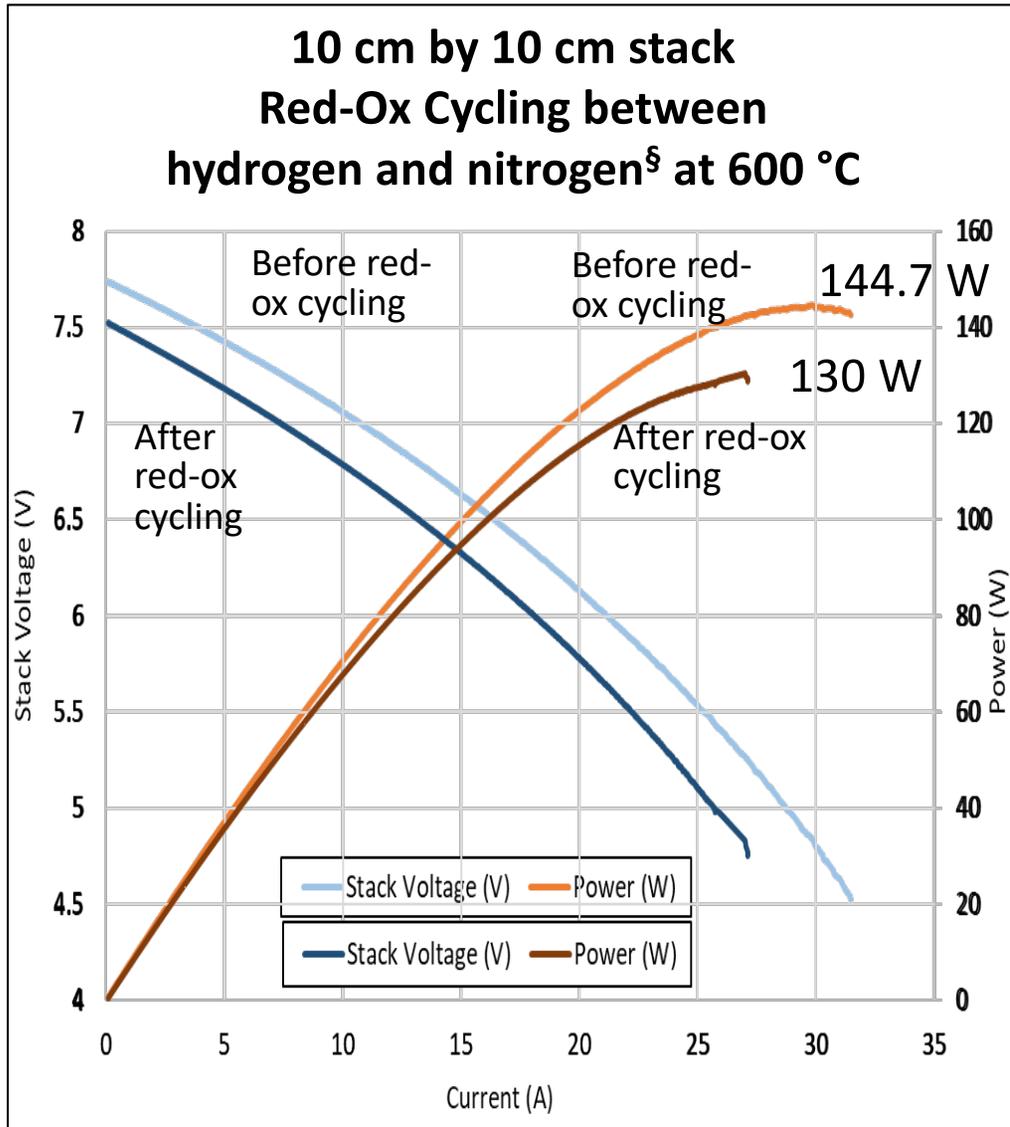
# Red-Ox Cycling



- Reduction-Oxidation cycles for ceramic anode material
- Single chamber environment, switching between H<sub>2</sub> and air (flush with N<sub>2</sub> first)

- Open Circuit Voltage during for 5 cm by 5 cm for 11 Red-Ox cycles (switching between H<sub>2</sub> and N<sub>2</sub>)
- Industrial grade N<sub>2</sub> has some oxygen
- This was done primarily due to the test setup configuration and no difference was observed from when air is used instead of N<sub>2</sub>

# Red-Ox Cycling of Stack



<sup>§</sup> Industrial grade N<sub>2</sub> has some oxygen

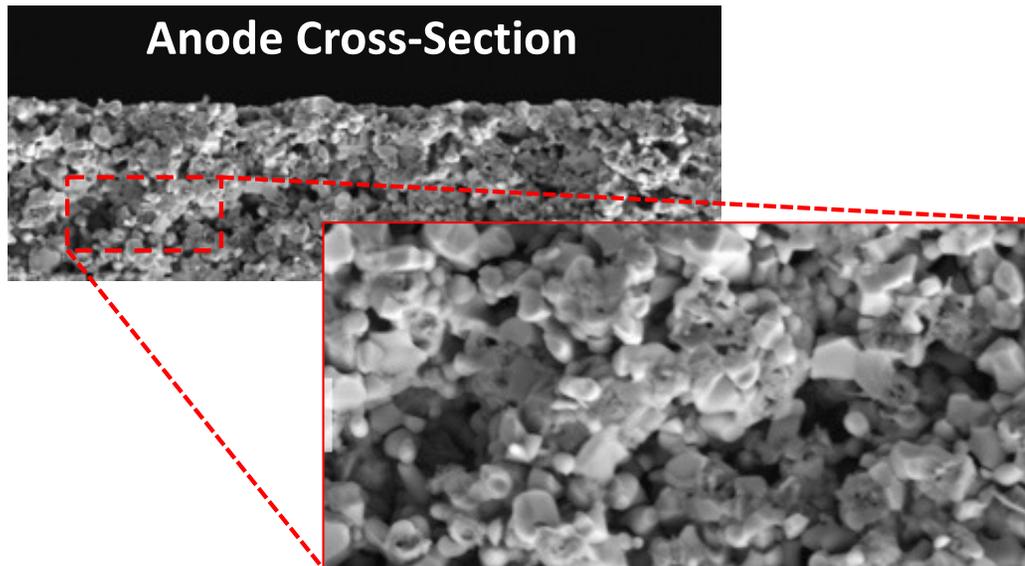
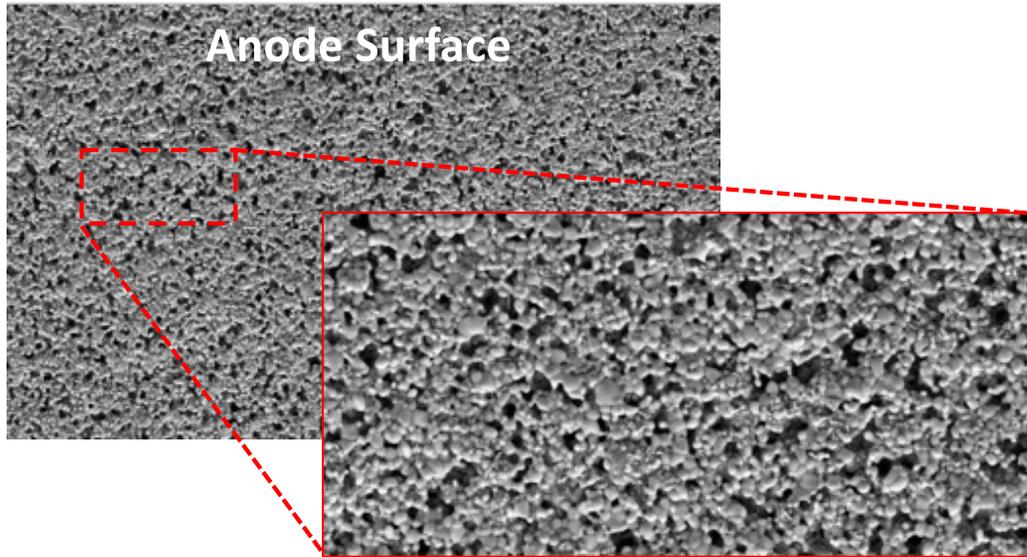
- Small performance drop after red-ox cycling
  - Possible small difference in operating temperature (thermal equilibrium not reached between cycles)
  - The ceramic anode may exhibit an initial decrease in conductivity after first cycle, followed by no changes (previous slide)
  - May also have been due to general long-term stability issues with large format cells
- Discovered problems with ceramic anode delamination during long-term operation in high humidity conditions experienced in large format cell operation and not observed in button cells
- Problem not in the ceramic-anode material itself (confirmed in 30% H<sub>2</sub>O, balance H<sub>2</sub>)
- Evidence that part of problem is due in part to bonding strength between layers
- To eliminate delamination, we explored modifications to the ceramic-anode configuration and processing conditions

# REDOX Competing Challenges for Ceramic-Anode SOFC

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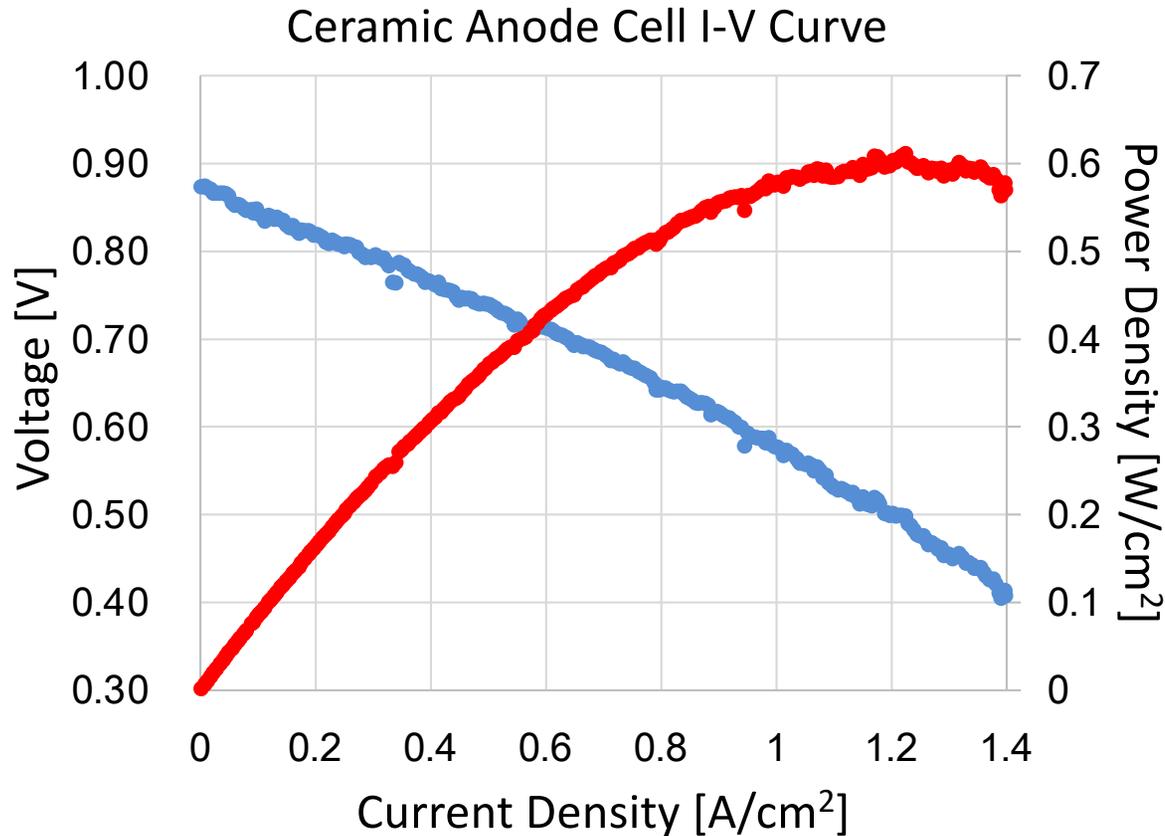
- Strength issues for large format cell
- Cell must be flat to prevent stress concentrators during stack assembly and operation
- Porosity must remain high for catalyst infiltration
- Shrinkage mismatch is challenging and normal methods for characterization (e.g., dilatometry) cannot always be relied upon to guide design and processing optimization
- Balance between pore-former size/amount, composite anode composition, layer thickness, and sintering process

# Red-Ox Cycling: Improved Ceramic-Anode Config.



- Red-Ox cycle conditions
  - The sample was heated to 600 °C in air, held for 3 hours; reducing gas (3% H<sub>2</sub> / 97% N<sub>2</sub>) was introduced and held for 3 hours; air was re-introduced
- 10 red-ox cycles
- After 10 red-ox cycles, no cracks are observed in anode surface or cross-section
- No delamination of any layers, or any other mechanical problem

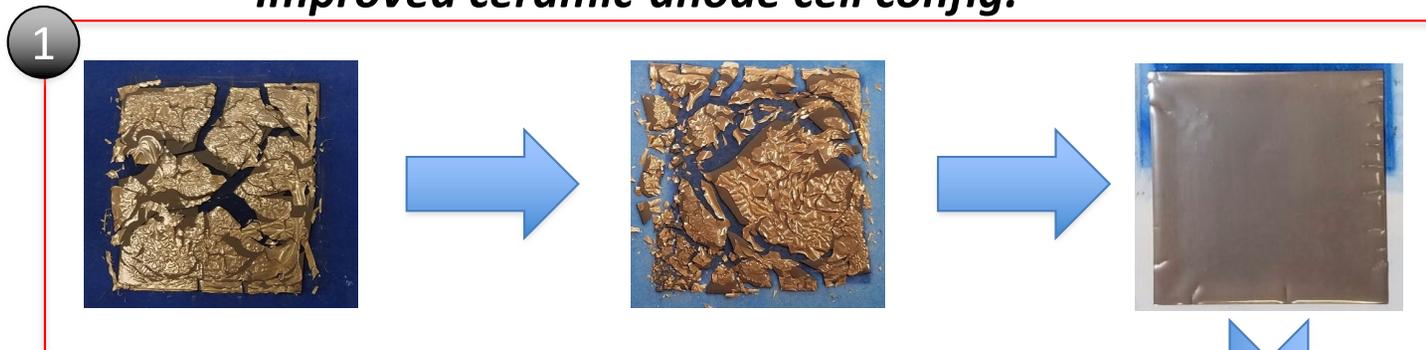
# Improved Ceramic-Anode Config. Performance



- 4 cm by 4 cm cell tested at 600 °C
- Better electrochemical performance compared to the original ceramic-anode configuration of the same size
  - > 5% increase in open circuit voltage
  - >35% increase in power density
  - Additional improvements possible

# Cell Size & Batch Size Scaleup

## *Improved ceramic-anode cell config.*

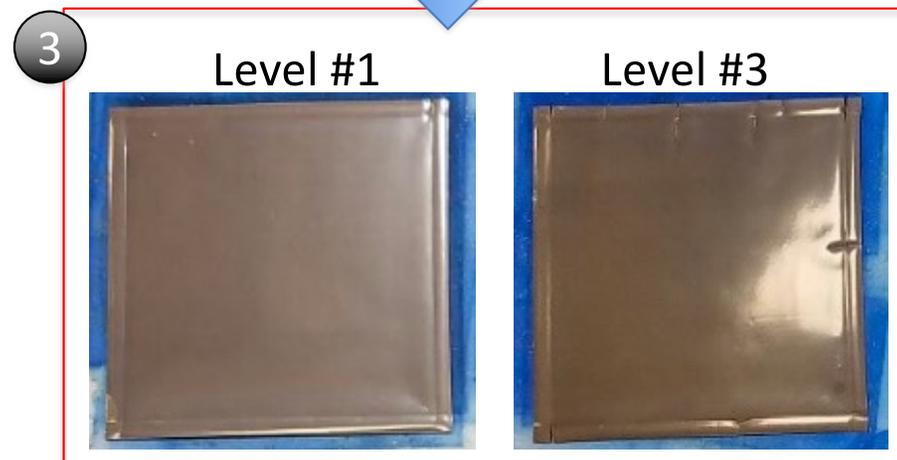


1. Composition optimization to prevent delamination (5 cm by 5 cm and 10 cm by 10 cm)

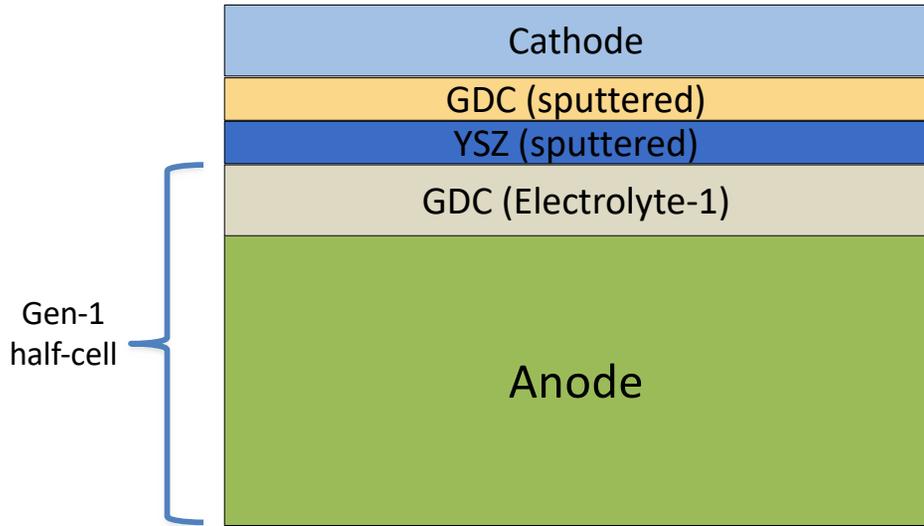
2. Fine tune composition / firing profile to reduce edge cracks

3. Optimize furnace temperature uniformity, tape caster thickness variation to increase yield in multi-level (4+) batch firing

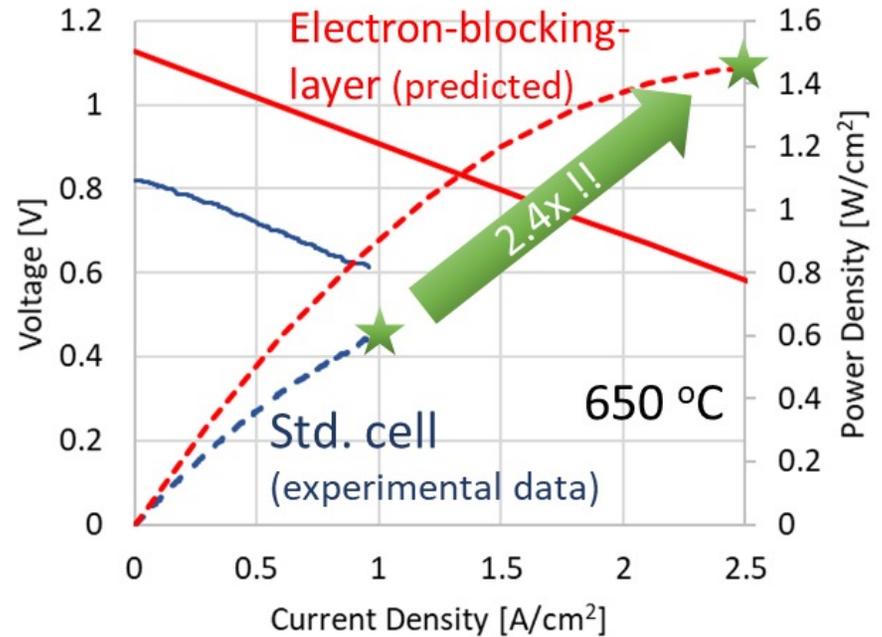
2



# FE0031656: Sputtered Thin Film SOFCs

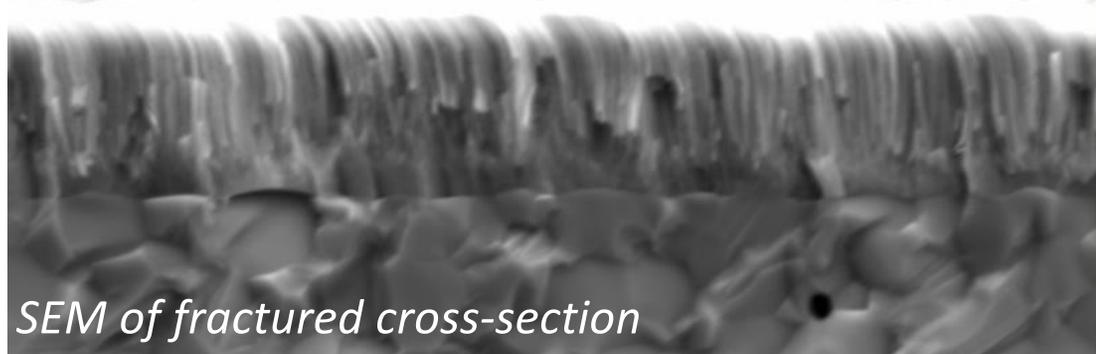


*Note: Layers are not shown to scale*



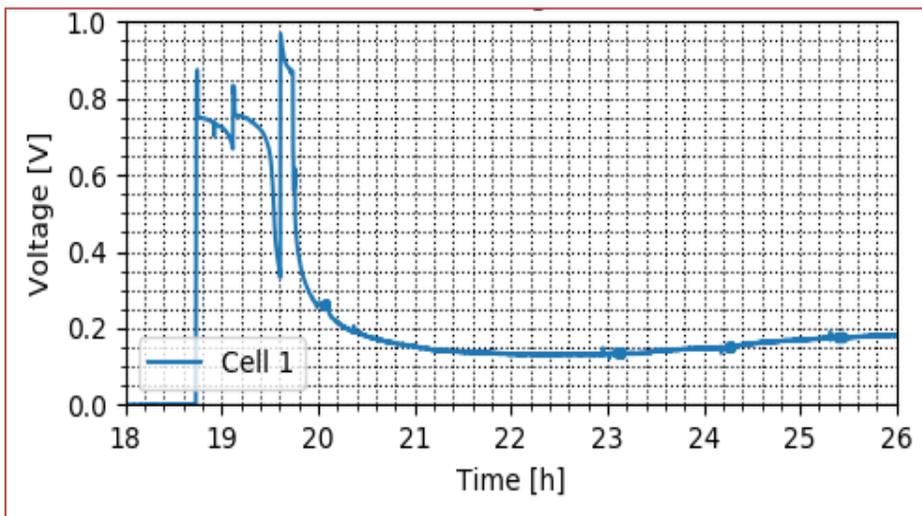
- Thin electron-blocking layer expected to increase Redox Gen-1 Ni-cermet cell power density by >2x
- Electron-blocking layer eliminates electronic leakage through ceria-based Electrolyte-1 → as much as ~40% increase in open circuit voltage is possible
- Very thin, dense electron-blocking layer adds negligible resistance
- Takes advantage of high-performance Redox Gen-1 cell platform
- Potential for even more power using Redox Gen-2 cell platform with porous, infiltrated anode (3.2 W/cm<sup>2</sup> at 650°C)

**GDC deposited on Gen-1 SOFC sample with YSZ layer previously deposited using commercial sputtering equipment**

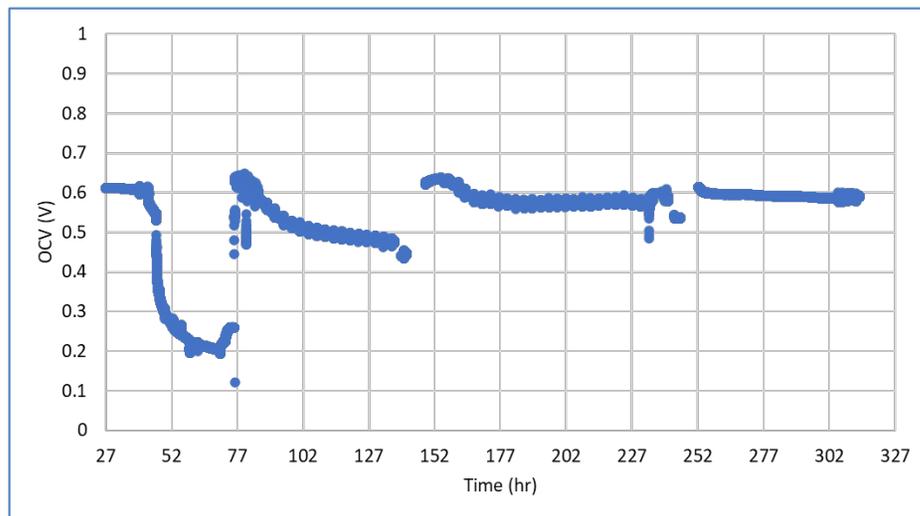


- ← GDC (buffer) film—lab equipment
- ← YSZ film—commercial equipment
- ← GDC electrolyte

- Successful deposition of GDC buffer layer with over 1  $\mu\text{m}/\text{hour}$  deposition rate on lab-scale system
- Required development of pre-sputter parameters and improvement of deposition conditions (e.g., Ar and  $\text{O}_2$  pressure and sputtering power)
- GDC film deposition subsequently optimized on commercial equipment to ensure dense, robust film with greater uniformity in larger size cells and faster deposition rates



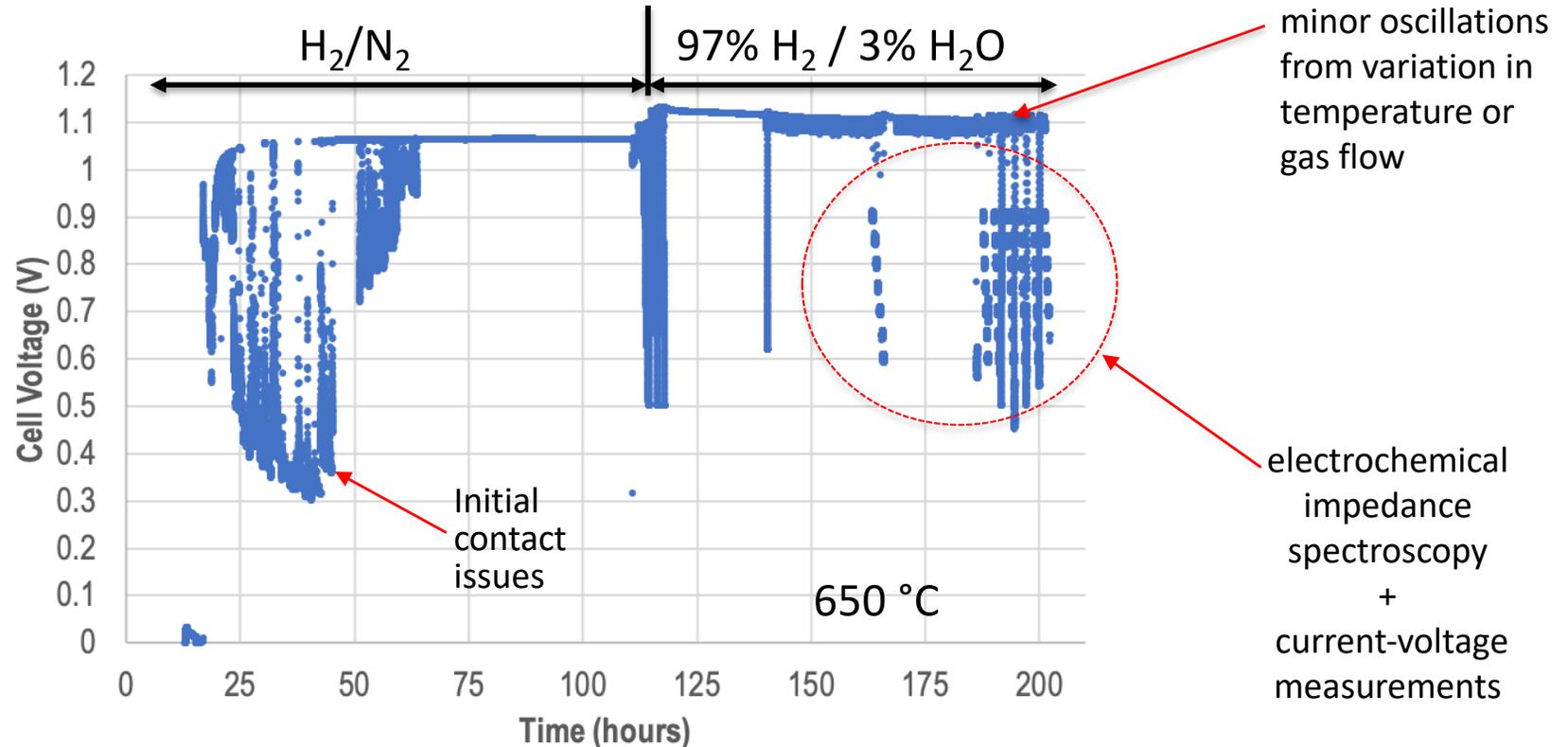
**Cell 1**  
4 cm by 4 cm



**Cell 2**  
4 cm by 4 cm

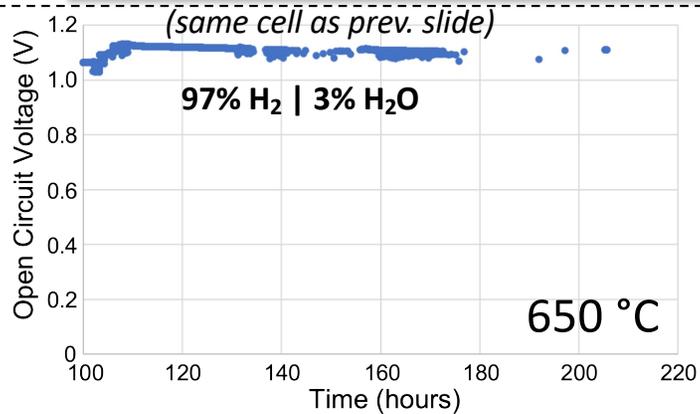
- Two types of issues were observed during initial tests
  - Stability Issues
    - Typically observed higher OCV initially, followed by rapid voltage drop to low values (e.g., Cell 1)
  - Lower OCV or similar OCV as standard, non-sputtered cells (same GDC electrolyte thickness)
    - Typically observed to have considerably lower OCV (e.g., Cell 2)

# REDOX Achieving $\geq 1V$ Open Circuit Voltage

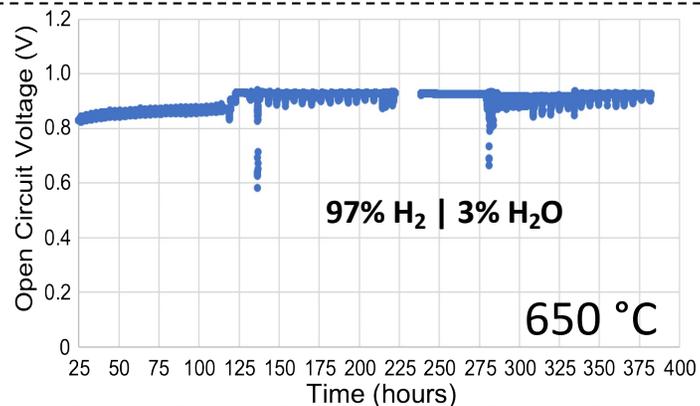


- Optimized sputtering conditions and post-sputter processing conditions
- 2 cm by 2 cm (sputtered YSZ & GDC) cell tested with stainless steel stack components
- Gas chromatography of the exhaust streams verified good sealing
- Theoretical OCV is 1.135V at 650 °C with 97% H<sub>2</sub> / 3% H<sub>2</sub>O at the anode and air at the cathode
- Therefore, the observed OCV was 99.6% of theoretical OCV, confirming an effective electron-blocking layer on the GDC electrolyte
- The OCV is stable and represents a > 30% increase over the baseline (same GDC electrolyte thickness)

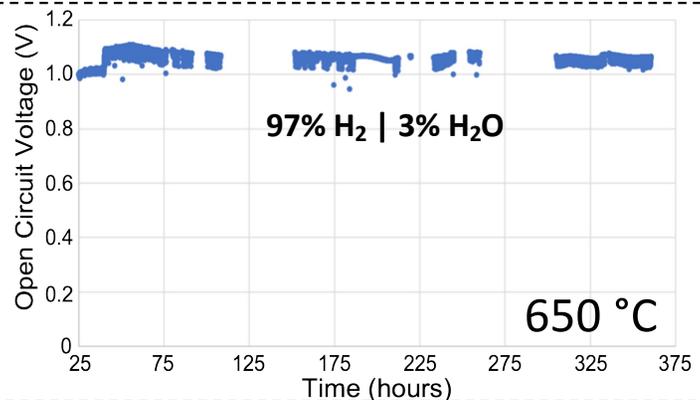
# REDOX Processing Improvements for Repeatable High OCV



- Type **A** sputtered layers\*
- OCV: 1.13 V
- Stable for > 100 hours before scheduled shutdown



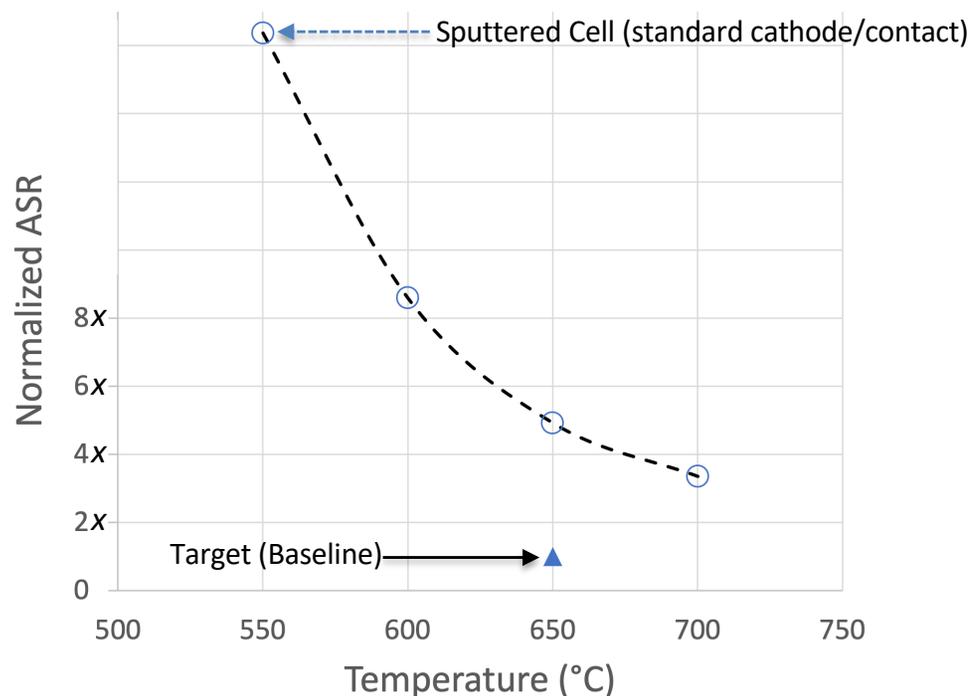
- Type **B** sputtered layers\*
- OCV: 0.95 V
- Stable for ~400 hours before scheduled shutdown



- Type **C** sputtered layers\*
- OCV: 1.10 V
- Stable for ~400 hours before scheduled shutdown

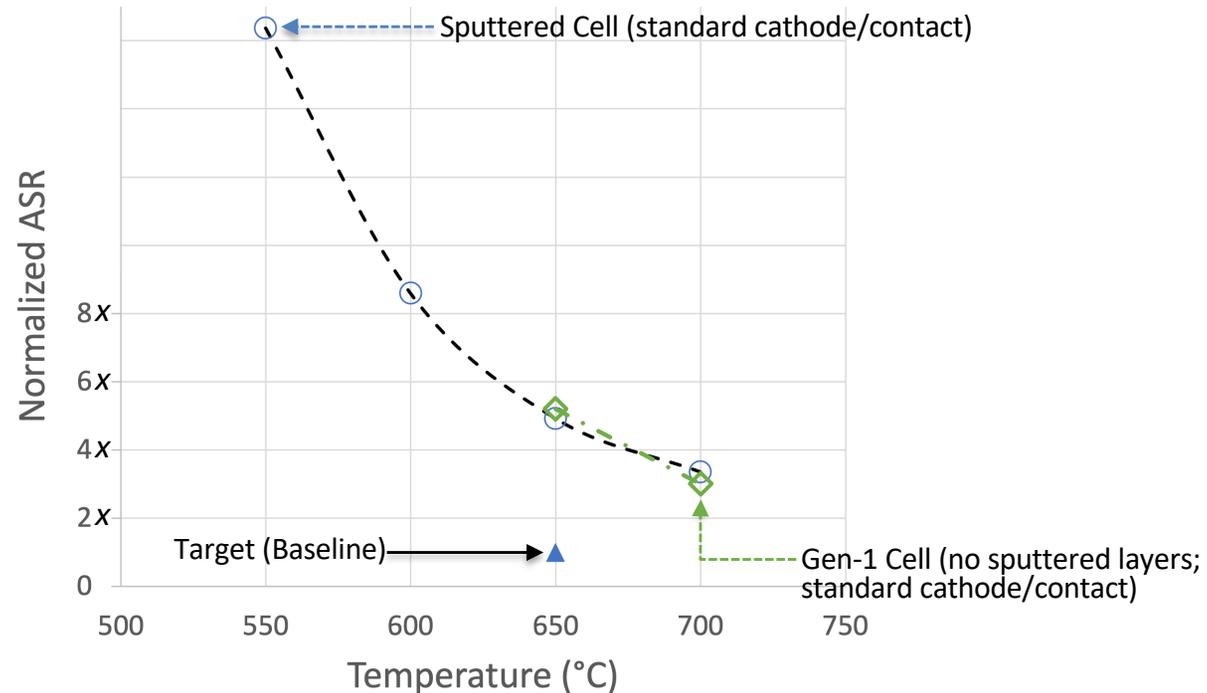
\*made using production sputtering equipment

# Higher Than Anticipated ASR



- Sputtered cell tested between 550 °C and 700 °C
- *High OCV*: ~1.13 V
- ASR of sputtered cell at 650 °C is about 5X higher at 650 °C than the target ASR (Redox Gen-1, non-sputtered)
- ASR did not change at 33% O<sub>2</sub> or 55% O<sub>2</sub> (mixed with air) or flow rate, suggesting the cathode is not the problem

# Higher Than Anticipated ASR



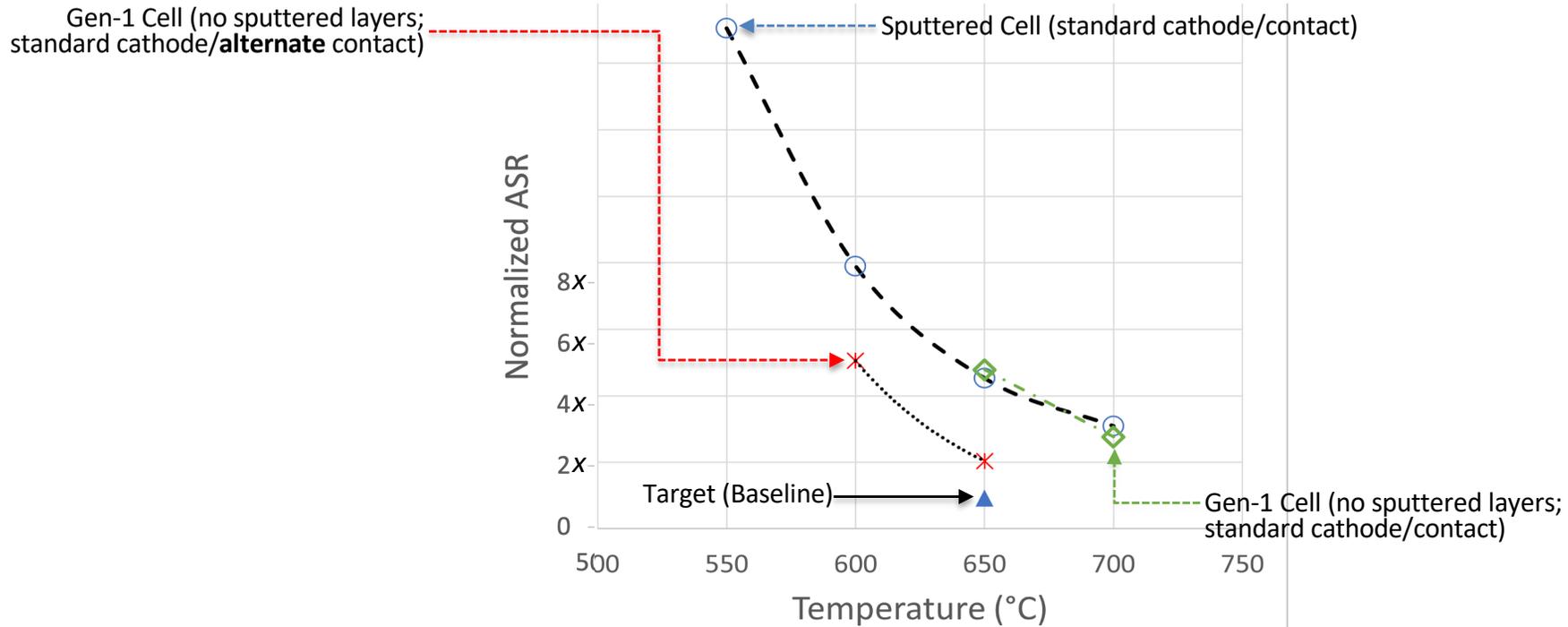
- Regular (non-sputtered) Gen-1 cell with same cathode/contact processing as sputtered cell
- Same ASR for the two cells at 650 °C and 700 °C
- Confirms the higher ASR is very likely due to cathode/contact processing

# Contact Adhesion Issues

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- We conducted several studies looking at cathode and contact adhesion at the various processing conditions used with sputtered cells
- Cathode/contact adhesion was found to be poor
- Adhesion of cathode (directly on GDC, without contact) was found to be sufficient
- Adhesion of standard contact (directly on GDC) was found to be poor
  - We therefore looked at some alternate contact materials
  - Several of the alternate contacts were found to have "good" adhesion
  - Adhesion remained "good" for the cathode/alternate contact

# Higher Than Anticipated ASR



- Standard Gen-1 cell (no sputtered layers) with standard cathode + alternate contact ("good" adhesion)
- Much lower ASR: ~2x the target ASR at 650 °C
- This result combined with adhesion test results provide strong evidence that the high ASR is due to the contact

- Repeat test with standard (non-sputtered cell)
  - fresh cathode paste to verify results
  - Standard contact & alternate contact
  - Use gold or silver contact
- Once the cathode and an alternate contact are found to match the target ASR, prepare additional sputtered cells
- Test these sputtered cells using the same procedures as the latest tests at several temperatures



# Summary of FE0027897 & FE0031656

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- FE0027897: Red-Ox Robust SOFCs
  - Red-Ox stability demonstrated
  - Improved performance demonstrated
  - Future room for improvement to balance strength and performance at large format cell size
  
- FE0031656: High-Power Thin-Film SOFCs
  - Optimized sputtering conditions to achieve dense YSZ electron-blocking layer and dense GDC buffer layer
  - Overcame low OCV issues and repeatably achieved theoretical OCV at 650 °C using target cell size
  - Demonstrated that the cathode contact is the cause for high ASR and that there is a path for reaching the target ASR with the sputtered cells

# Acknowledgements

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**NETL program manager: Jason Montgomery**

- **DE-FE0027897**
- **DE-FE0031656**

